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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary) 26

Sheet 1 of

2

Application Number	09/698,317
Filing Date	October 27, 2000
First Named Inventor	Choi et al.
Group Art Unit	2859
Examiner Name	Unassigned <i>T. Dougherty</i>
Attorney Docket Number	PA09-06V02

U.S. PATENT DOCUMENTS

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FOREIGN PATENT DOCUMENTS

[illegible]

**Examiner
Signature**

Thomas M. H. Brecherts

Date
Considered

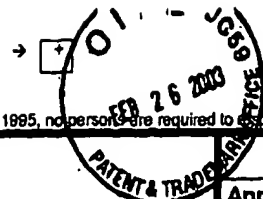
2-12-04

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¹Unique citation designation number. ²See attached Kinds of U.S. Patent Documents. ³Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 18 if possible. ⁶Applicant is to place a check mark here if English language Translation is attached.

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Substitute for form 1449B/PTO		Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Application Number	09/698,317
		Filing Date	October 27, 2000
		First Named Inventor	Choi et al.
		Group Art Unit	2859
		Examiner Name	Unassigned T. Dougherty
Sheet 2 of 2	Attorney Docket Number	PA09-06V02	

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cita No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
TMD	B10	LIN, "Multi-Layer Resist Systems", Introduction of Microlithography, American Chemical Society, 1983, pp. 287-350, IBM T.J. Watson Research Center, Yorktown Heights, New York 10598.	
TMD	B11	COWIE, "Polymers: Chemistry and Physics of Modern Materials", 1991, pp. 408-409, 2 nd Ed, Chapman and Hall, a division of Routledge, Chapman and Hall, Inc., 29 West 35 th Street, NY, NY 10001-2291.	
TMD	B12	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers", Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).	
TMD	B13	CHOU et al., "Imprint Lithography with 25-Nanometer Resolution", Science, Apr. 5, 1996, pp. 85-87, vol. 272.	
TMD	B14	CHOU et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput", Microelectronic Engineering, 1997, pp. 237-240, vol. 35.	
TMD	B15	XIA et al., "Soft Lithography", Agnew. Chem. Int. Ed., 1998, pp. 550-575, vol. 37.	

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Examiner Signature	Thomas M. Dougherty	Date Considered	2-12-04
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Substitute for form 1449A/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 1 of 2

Complete if Known

Application Number	09/698,317
Filing Date	October 27, 2000
First Named Inventor	Choi et al.
Group Art Unit	2834
Examiner Name	Dougherty, Thomas M.
Attorney Docket Number	UTS-09-06V02

U.S. PATENT DOCUMENTS

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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹Unique citation designation number. ²See attached Kinds of U.S. Patent Documents. ³Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 18 if possible. ⁶Applicant is to place a check mark here if English language Translation is attached.

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Thomas M. Dougherty February 12, 2004

Approved for use

Substitute for form 1449B/PTO				<div> <div>Complete if Known</div> <table border="1"> <tr> <td>Applicati n Number</td> <td>09/698,317</td> </tr> <tr> <td>Filing Dat</td> <td>October 27, 2000</td> </tr> <tr> <td>First Nam d Inv nt r</td> <td>Choi et al.</td> </tr> <tr> <td>Group Art Unit</td> <td>2834</td> </tr> <tr> <td>Examiner Name</td> <td>Dougherty, Thomas M.</td> </tr> <tr> <td>Attorney Docket Number</td> <td>UTS-09-06V02</td> </tr> </table> </div>		Applicati n Number	09/698,317	Filing Dat	October 27, 2000	First Nam d Inv nt r	Choi et al.	Group Art Unit	2834	Examiner Name	Dougherty, Thomas M.	Attorney Docket Number	UTS-09-06V02
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Examiner Name	Dougherty, Thomas M.																
Attorney Docket Number	UTS-09-06V02																
<div> <div> <div>INFORMATION DISCLOSURE</div> <div>STATEMENT BY APPLICANT</div> </div> <div> <div>DEC 22 2003</div> <div>(use as many sheets as necessary)</div> </div> </div>																	
Sheet	2	of	2														

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Examiner Signature	<i>Thomas M. Kersch</i>	Date Considered	<i>Feb. 12, 2004</i>
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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Form PTO-1449 (modified)

List of Patents and Publications

For Applicant's Information

Disclosure Statement

(Use several sheets if necessary)

ATTY. DKT. NO. 5119-08601

APPLICANT: Choi et al.

FILING DATE: October 27, 2000

SERIAL NO. 09/698,317

GROUP: 2859

U.S. PATENT DOCUMENTS

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
tmp	A1	3,807,027	4/1974	Heisler	29	423	
tmp	A2	3,807,029	4/1974	Troeger	29	436	
tmp	A3	3,811,665	5/1974	Seelig	26	RECEIVED	
tmp	A4	4,062,600	12/1977	Wyse	384	325	2002
tmp	A5	4,098,001	7/1978	Watson	33	644	
tmp	A6	4,155,169	5/1979	Drake et al.	33	GROUP 3600	
tmp	A7	4,202,107	5/1980	Watson	33	644	
tmp	A8	4,267,212	5/1981	Sakawaki	427	240	
tmp	A9	4,337,579	7/1982	De Fazio	33	644	
tmp	A10	4,355,469	10/1982	Nevins et al.	267	150	
tmp	A11	4,414,750	11/1983	De Fazio	267	166	
tmp	A12	4,451,507	5/1984	Beltz et al.	427	240	
tmp	A13	4,610,442	9/1986	Oku et al.	269	73	
tmp	A14	4,694,703	11/1987	Routson	79	5F	
tmp	A15	4,731,155	3/1988	Napoli et al.	216	44	
tmp	A16	4,763,886	8/1988	Takei	269	73	
tmp	A17	4,929,083	5/1990	Brunner	356	400	
tmp	A18	4,959,252	11/1990	Bonnebat et al.	428	64.7	
tmp	A19	5,072,126	12/1991	Progler	250	548	
tmp	A20	5,110,514	5/1992	Soane	264	496	
tmp	A21	5,126,006	6/1992	Cronin et al.	438	702	
tmp	A22	5,204,739	4/1993	Domenicali	348	79	
tmp	A23	5,240,550	8/1993	Boehnke et al.	216	24	
tmp	A24	5,348,616	9/1994	Hartman et al.	216	48	
tmp	A25	5,392,123	2/1995	Marcus et al.	356	625	
tmp	A26	5,425,964	6/1995	Southwell et al.	427	10	
tmp	A27	5,452,090	9/1995	Progler et al.	356	401	

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Pheman M. Ruppert

DATE CONSIDERED:

Feb. 13, 2001

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Information Disclosure Statement--PTO 1449 (modified)

Form PTO-1449 (modified)

List of Patents and Publications
For Applicant's Information
Disclosure Statement
(Use several sheets if necessary)

ATTY. DKT. NO. 5119-08601

SERIAL NO. 09/698,317

APPLICANT: Choi et al.

GROUP: 2859

FILING DATE: October 27, 2000

U.S. PATENT DOCUMENTS

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
DMB	A28	5,480,047	1/1996	Tanigawa et al.	216	12	
DMB	A29	5,512,131	4/1996	Kumar et al.	438	595	
DMB	A30	5,515,167	5/1996	Ledger et al.	356	595	
DMB	A31	5,545,367	10/1996	Bae et al.	264	401	
DMB	A32	5,566,584	10/1996	Briganti et al.	74	401	
DMB	A33	5,633,505	5/1997	Chung et al.	250	491.1	
DMB	A34	5,724,145	3/1998	Kondo et al.	356	632	
DMB	A35	5,753,014	5/1998	Van Rijn	96	12	
DMB	A36	5,760,500	6/1998	Kondo et al.	310	12	
DMB	A37	5,772,905	6/1998	Chou	216	44	
DMB	A38	5,776,748	7/1998	Singhvi et al.	435	180	
DMB	A39	5,779,799	7/1998	Davis	118	663	
DMB	A40	5,802,914	9/1998	Fassler et al.	74	110	
DMB	A41	5,877,036	3/1999	Kawai	438	16	
DMB	A42	5,877,861	3/1999	Ausschnitt et al.	356	401	
DMB	A43	5,888,650	3/1999	Calhoun et al.	428	354	
DMB	A44	5,900,160	5/1999	Whitesides et al.	216	41	
DMB	A45	5,912,049	6/1999	Shirley	427	240	
DMB	A46	5,942,871	8/1999	Lee	318	611	
DMB	A47	5,948,470	9/1999	Harrison et al.	427	198	
DMB	A48	5,952,127	9/1999	Yamanaka	430	5	
DMB	A49	6,038,280	3/2000	Rossiger et al.	378	50	
DMB	A50	6,039,897	3/2000	Lochhead et al.	264	1,24	
DMB	A51	6,046,056	4/2000	Parce et al.	204	402.05	
DMB	A52	6,051,345	4/2000	Huang	430	5	
DMB	A53	6,074,827	6/2000	Nelson et al.	435	6	
DMB	A54	6,091,485	7/2000	Li et al.	356	73	
	A55	6,128,085	10/2000	Buermann et al.	356	369	

EXAMINER:

Shuman M. Dwyer

DATE CONSIDERED:

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Information Disclosure Statement-PTO 1449 (modified)

Form PTO-1449 (modified)

List of Patents and Publications

For Applicant's Information

Disclosure Statement

(Use several sheets if necessary)

ATTY. DKT. NO. 5119-08601

SERIAL NO. 09/698,317

APPLICANT: Choi et al.

GROUP: 2859

FILING DATE: October 27, 2000

U.S. PATENT DOCUMENTS

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>mb</i>	A56	6,143,412	11/2000	Schueller et al.	428	408	
<i>mb</i>	A57	6,168,845	1/2001	Fontana, Jr. et al.	428	65.5	
<i>mb</i>	A58	6,180,239	1/2001	Whitesides et al.	428	411.1	JUN 26 2002
<i>mb</i>	A59	6,204,922	3/2001	Chalmers	356		
<i>mb</i>	A60	6,334,960	1/2002	Wilson et al.	216	52	

FOREIGN PATENT DOCUMENTS

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO
<i>mb</i>	A61	00/54107	9/2000	WO	600F	7/00	
<i>mb</i>	A62	01/33232	5/2001	WO	601R	—	
<i>mb</i>	A63	01/33300	5/2001	WO	402K	5/24	
<i>mb</i>	A64	244884	3/1987	EP	829C	33/34	
<i>mb</i>	A65	733455	9/1996	EP	829C	33/34	NO
<i>mb</i>	A66	2800476	7/1978	DE	603C	5/08	NO
<i>mb</i>	A67	19648844	11/1999	DE	829C	59/02	NO
<i>mb</i>	A68	1-196749	8/1989	JP	511B	7/26	NO

EXAMINER:

Thomas M. Dougherty

DATE CONSIDERED:

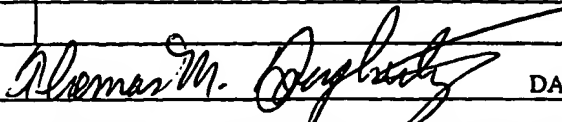
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Information Disclosure Statement--PTO 1449 (modified)

Form PTO-1449 (modified) List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)		ATTY. DKT. NO. 5119-08601 APPLICANT: Choi et al. FILING DATE: October 27, 2000	RECEIVED GROUP 3600 JUN 26 2002 09/698,317 2859
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)			
tmh	A69	Stewart, D.; "A Platform with Six Degrees of Freedom", Proc. of Inst. Mech. Engrs., 1965, 180, 371-378.	
tmh	A70	Paros, J.M.; Weisbord, L.; "How to Design Flexure Hinges", Machine Design, 1965, 151-156.	
tmh	A71	Raibert, M.H.; Craig, J.J.; "Hybrid Position/Force Control of Manipulators", 1981, 102, 126-133.	
tmh	A72	Hogan, Neville; "Impedance Control: An Approach to Manipulation", Journal of Dynamic Systems, Measurement and Control, 1985, 107, 1-7.	
tmh	A73	Hollis, Ralph; Salcudean, S.E.; Allan, A.P.; "A Six-Degree-of-Freedom Magnetically Levitated Variable Compliance Fine-Motion Wrist: Design, Modeling and Control", IEEE Transactions on Robotics and Automation, 1991, 7, 320-332.	
tmh	A74	Tomita, Y. et al.; "6-Axes Motion Control Method for Parallel-Linkage-Type Fine Motion Stage", Journal of Japan Society of Precision Engineering, 1992, 118-124.	
tmh	A75	Slocum, Alexander; "Precision Machine Design: Macromachine Design Philosophy and its Applicability to the Design of Micromachines", Proc. of IEEE Micro Electro Mech. Systems Workshop, 1992, 37-42.	
tmh	A76	Krug, Herbert; Merl, Norbert; Schmidt, Helmut; "Fine Patterning of Thin Sol-Gel Films", Journal of Non-Crystalline Solids, 1992, 447-450.	
tmh	A77	Arai, T.; Larssonneur, R.; Jaya, Y.M.; "Calibration and Basic Motion of a Micro Hand Module", Proc. of IECON, 1993, 1660-1665.	
tmh	A78	Peng, Zhi-Xin; Adachi, N.; "Compliant Motion Control of Kinematically Redundant Manipulators", IEEE Transactions on Robotics and Automation, 1993, 9, 831-837.	
tmh	A79	Rong, Y.; Zhu, Y.; Luo, Z.; Liu, X.; "Design and Analysis of Flexure-Hinge Mechanism Used in Micro-Positioning Stages", ASME, 1994, 2, 979-985.	
tmh	A80	Hashimoto, M.; Imamura, Y.; "Design and Characteristics of a Parallel Link Compliant Wrist", IEEE International Conference on Robotics and Automation, 1994, 2457-2462.	
tmh	A81	Merlet, J.P.; "Parallel Manipulators: State of the Art and Perspectives", Advanced Robotics, 1994, 8, 589-596.	
tmh	A82	Ananthasuresh, S.; Kikuchi, N.; "Strategies for Systematic Synthesis of Compliant MEMS", ASME, 1994, 2, 677-686.	
tmh	A83	Arai, T.; Tanikawa, T.; Merlet, J.P.; Sendai, T.; "Development of a New Parallel Manipulator with Fixed Linear Actuator", Proc. of Japan/USA Symposium on Flexible Automation, 1996, 1, 145-149.	
tmh	A84	Howell, L.L.; Midha, A.; "Loop-Closure Theory of the Analysis and Synthesis of Compliant Mechanisms", Journal of Mechanical Design, 1996, 118, 121-125.	
tmh	A85	Haisma, J. et al.; "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication", Journal of Vacuum Science and Technology, 1996, 14, 4124-4128.	
tmh	A86	Pernette, Eric; Henein, Simon; Magnani, Ivo; Clavel, Reymond; "Design of Parallel Robots in Microrobotics", Robotica, 1997, 15, 417-420.	

EXAMINER:



DATE CONSIDERED:

Feb. 13, 2004

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Information Disclosure Statement--PTO 1449 (modified)

Form PTO-1449 (modified) List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)		ATTY. DKT. NO. 5119-08601 APPLICANT: Choi et al. FILING DATE: October 27, 2000	SERIAL NO. 09/698,317 GROUP: 2859
TMB A87	Rong, L.; Guanghui; "Dynamics of Parallel Mechanism with Direct Compliance Control", IEEE, 1997, 1753-1758.		
TMB A88	Mittal, Samir; Menq, Chia-Hsiang; "Precision Motion Control of Magnetic Suspension Actuator Using a Robust Nonlinear Compensation Scheme", IEEE/ASME Transactions on Mechatronics, 1997, 2, 268-280.		
TMB A89	Physik Instruments, Product Catalog for Micropositioning, 1997.		
TMB A90	Williams, Mark et al.; "Six Degree of Freedom Mag-Lev Stage Development", SPIE, 1997, 3051, 856-867.		
TMB A91	Lee, Chang-Woo; Kim, Seung-Woo; "Ultraprecision Stage for Alignment of Wafers in Advanced Microlithography", Precision Engineering, 1997, 21, 113-122.		
TMB A92	Kanetomo, M.; Kashima, H.; Suzuki, T.; "Robot for Use in Ultrahigh Vacuum", Solid State Tech., 1997, 63-72.		
TMB A93	Goldfarb, M.; Speich, J.; "Compliant Micromanipulator Design for Scaled Bilateral Telemanipulation of Small-Scale Environments", ASME, Dynamic Systems and Control Div., 1998, 64, 213-218.		
TMB A94	Koseki, Y. et al.; "Design and Accuracy Evaluation of High-Speed and High Precision Parallel Mechanism", Proc. of IEEE, Intl. Conf. on Robotics & Automation, 1998, 1340-1345.		
TMB A95	Kim, Won-Jong; Trumper, David; "High Precision Magnetic Levitation Stage for Photolithography", Precision Engineering, 1998, 22, 66-77.		
TMB A96	Mansky, P. et al.; "Large-Area Domain Alignment in Block Copolymer Thin Films Using Electric Fields", Macromolecules, 1998, 31, 4399-4401.		
TMB A97	Wang, W.; Loh, R.; Gu, E.; "Passive Compliance Versus Active Compliance in Robot-Based Automated Assembly Systems", Industrial Robot, 1998, 25, 48-57.		
TMB A98	Scheer, H.C. et al.; "Problems of Nanoimprinting Technique for Nanometer Scale Pattern Definition", Journal of Vacuum Science and Technology, 1998, 16, 3917-3921.		
TMB A99	Xia, Y.; Whitesides, George; "Soft Lithography", Annu. Rev. Mater. Sci., 1998, 28, 153-184.		
TMB A100	Tajbakhsh, H. et al.; "Three-Degree-of-Freedom Optic Mount for Extreme Ultraviolet Lithography", ASPE, 1998, 18, 359-362.		
TMB A101	Lee, Dong Sung et al.; "Ultra Precision Positioning System for Servo Motor-Piezo Actuator Using Dual Servo Loop and Digital Filter Implementation", ASPE, 1998, 18, 287-290.		
TMB A102	Wu, Wei et al.; "Large Area High Density Quantized Magnetic Disks Fabricated Using Nanoimprint Lithography", 1998, Journal of Vacuum Science and Technology, 1998, 16, 3825-3829.		
TMB A103	Ohya, Y. et al.; "Development of 3-DOF Finger Module for Micro Manipulation", Proc. of IEEE, Intl. Conf. on Intelligent Robots and Systems, 1999, 894-899.		
TMB A104	Tanikawa, T. et al.; "Development of Small-Sized 3 DOF Finger Module in Micro Hand for Micro Manipulation", Proc. of IEEE, Intl. Conf. on Intelligent Robots and Systems, 1999, 876-881.		
TMB A105	Colburn, M. et al.; "Step and Flash Imprint Lithography: New Approach to High-Resolution Patterning", Proc. of SPIE, 1999, 3676, 379-389.		

EXAMINER:

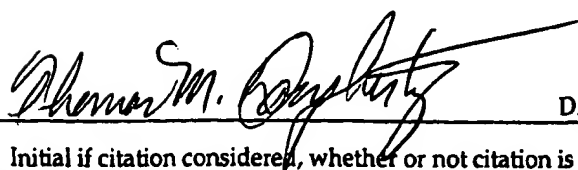
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Information Disclosure Statement--PTO 1449 (modified)

Form PTO-1449 (modified) List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)		PAT. & TRADEMARK OFFICE JUN 21 2002	PAT. DKT. NO. 5119-0860 APPLICANT: Choi et al. FILING DATE: October 27, 2000	SERIAL NO. 09/698,317 GROUP: 2859 JUN 26 2002 GROUP 3600
IMB	A106	Lucas Aerospace, Free-Flex Pivot Catalog. 1999		
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IMB	A108	Geodetic Technology, G1000-PS Power Series Specifications, 1999, from www.hexapods.com		
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Feb. 13, 2004

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Information Disclosure Statement--PTO 1449 (modified)